AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A semiconductor device comprising:

a high-breakdown-voltage regulator configured to operate at a high input voltage to produce a regulated output voltage that is lower than the high input voltage, said high-breakdown-voltage regulator comprising resistors connected in series to divide a voltage output from a transistor connected to <a href="https://high-put.nih.gip.nih.

a low-breakdown-voltage regulator comprising a second reference voltage generating circuit configured to receive the regulated output voltage from the high-breakdown-voltage regulator to generate a second reference voltage and a second differential amplifier circuit configured to receive the second reference voltage from the second reference voltage generating circuit to produce a drive voltage;

an output driver structured as a high-breakdown-voltage component and configured to operate based on the drive voltage, wherein the output driver is a MOS transistor; and resistors connected in series to the output driver to divide an output voltage of the output

driver and feed the divided voltage back to the second differential amplifier circuit.

- (Previously Presented) The semiconductor device of claim 1, wherein the highbreakdown-voltage output driver is a MOS transistor with a gate oxide film having a first thickness.
- (Previously Presented) The semiconductor device of claim 2, wherein the high-breakdown-voltage regulator comprises a high-breakdown-voltage MOS transistor with a gate oxide film having a second thickness greater than the first thickness.

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4. (Previously Presented) The semiconductor device of claim 1, wherein the output driver is a P-channel MOS transistor, the semiconductor device further comprising a diode inserted between the gate and the source of the P-channel MOS transistor having a reverse breakdown voltage lower than an oxide breakdown voltage of the P-channel MOS transistor.

- 5. (Previously Presented) The semiconductor device of claim 1, wherein the output driver is an N-channel MOS transistor, the semiconductor device further comprising a diode inserted between the gate and the source of the N-channel MOS transistor or between the gate and the ground and having a reverse breakdown voltage lower than an oxide breakdown voltage of the N-channel MOS transistor.
- 6. (Previously Presented) The semiconductor device of claim 1, wherein the output driver is a P-channel MOS transistor, the semiconductor device further comprising a constant current inverter inserted between the differential amplifier circuit and the output driver, the constant current inverter comprising:

a constant current circuit connected between a power supply line and the output driver; and a MOS transistor controlled by the drive voltage output from the differential amplifier circuit.

7. (Previously Presented) The semiconductor device of claim 1, wherein the output driver is a P-channel MOS transistor, the semiconductor device further comprising a constant current inverter inserted between a power supply line and the output driver, the constant current inverter comprising:

a first N-channel MOS transistor to which the reference voltage generated by the first reference voltage generating circuit is supplied:

a first P-channel MOS transistor connected in series to the first N-channel MOS transistor to produce a constant current;

a second P-channel MOS transistor defining a constant current circuit under a current mirror configuration; and

a second N-channel MOS transistor to which the drive voltage output from the second differential amplifier circuit is supplied.

8. (Currently Amended) A semiconductor device comprising:

a first reference voltage generating circuit configured to generate a first reference voltage from a high input voltage, said first reference voltage being lower than the high input voltage;

a second reference voltage generating circuit configured to generate a second reference voltage, said second reference voltage generating circuit comprising resistors connected in series to divide a voltage output from a transistor connected to the high input voltage a-power-supply-line, said transistor having a gate connected to an output of a first differential amplifier circuit receiving a first input from said first reference voltage generating circuit and a second input as a feedback voltage divided by said resistors, said first differential amplifier being driven by said high input voltage:

a second differential amplifier circuit configured to receive the second reference voltage and generate a drive voltage;

an output driver configured to operate based on the drive voltage, wherein the output driver is a MOS transistor:

a diode inserted between a gate and a source of the MOS transistor, the diode having a reverse breakdown voltage lower than an oxide breakdown voltage of the MOS transistor;

resistors connected in series to the output driver to divide an output voltage of the output driver and feed the divided voltage back to the second differential amplifier circuit; and

a constant current circuit inserted between a power supply-line and a combination of the reference voltage generating circuit and the second differential amplifier circuit.

- (Original) The semiconductor device of claim 8, wherein the constant current circuit is structure by a depression-mode N-channel or P-channel MOS transistor.
- (Original) The semiconductor device of claim 8, wherein the constant current circuit is structured by an enhancement-mode N-channel or P-channel MOS transistor.

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11. (Previously Presented) The semiconductor device of claim 8, wherein the constant current circuit includes multiple MOS transistors connected in series to form a multi-stage constant current

circuit.

12. (Previously Presented) The semiconductor device of claim 2, wherein the low-breakdown

voltage regulator comprises a MOS transistor having a gate oxide film of the first thickness.